OUENCH STUDIES OF SIX HIGH TEMPERATURE NITROGEN DOPED 9 CELL CAVITIES FOR USE IN THE LCLS-II BASELINE PROTOTYPE CRYO-MODULE AT JEFFERSON LABORATORY

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Abstract

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author(s), title of the work, publisher, and Jefferson Lab (JLab) processed six nine-cell cavities as gpart of a small-scale production for LCLS-II cavity \mathfrak{S} processing development utilizing the promising 5 nitrogen-doping process. [1] Various nitrogen-doping recipes have been scrutinized to optimize process grameters with the aim to guarantee an unloaded quality factor (Q_0) of 2.7e10 at an accelerating field (Eacc) of intain 16 MV/m at 2.0 K in the cryomodule. During the R&D ma phase the characteristic Q0 vs. Eacc performance curve g of the cavities has been measured in JLab's vertical test area at 2 K. The findings showed the characteristic rise area at 2 K. The findings showed the characteristic rise vork of the Q0 with Eacc as expected from nitrogen-doping. Initially, five cavities achieved an average Q0 of 3.3e10 S. at the limiting Eacc averaging to 16.8 MV/m, while one cavity experienced an early quench accompanied by an unusual Q_0 vs. Eacc curve. The project accounts for a cavity performance loss from the vertical dewar test (with or without the helium vessel) to the horizontal performance ≥in a cryomodule, such that these results leave no save margin to the cryomodule specification. Consequently, a $\hat{\mathbf{v}}$ refinement of the nitrogen-doping has been initiated to 20 guarantee an average quench field above 20 MV/m without impeding the Q_0. This paper covers the refinement work licence performed for each cavity, which depends on the initial results, as well as a quench analysis carried out before 3.0] and after the rework during the vertical RF tests as far as applicable. ВΥ

INTRODUCTION

terms of the CC JLab is collaborating with FNAL and Cornell to expedite the development and exploitation of methods to produce dramatically lower-loss SRF cavities using the nitrogen-doping (N-doping) technique discovered by FNAL. [1] The LCLS-II project is eager to take advantage of these developments to minimize cryogenic capital and used operating costs. JLab's contribution to this effort centered on systematic processing and tests of a set of single-cell ő ≥1.3 GHz cavities, followed by a "'production-style"' run treating six existing TESLA-style nine-cell cavities work (AES031-036) to assess the performance in dependence



Figure 1: All RF test results for the 6 - 9 cell cavities.

on various nitrogen-doping recipes. Based on the single cell tests, a recipe for the nine-cell cavities has been determined which meets the desired project specifications. The initial nine-cell surface processing consisted of a UHV furnace heat treatment at 800 deg. C for 3 hours followed by controlled nitrogen injection for 20 minute at an average N2-pressure of 26 mTorr with an additional 30 minute annealing time under vacuum before letting the furnace cool down unconstrained with active pumping. After the N-doping each cavity received a 16 μ m interior surface removal by Electropolishing (EP) to remove the topical highly nitrogen-enriched surface layer. [3] The nomenclature used in the following refers to the nitrogen injection time (N), annealing time (A) and EP surface removal, e.g. here N20A30_EP16. Three of the first nine-cell tests were published already. [4]

At this time is became clear that although a sufficiently high Q_0 could be guaranteed at 16 MV/m, but the average quench field ($Q_o > 16=MV/m$) was too close to the LCLS-II operating specification. In addition one has to consider that all N-doped cavities quenched at a much lower field than routinely achievable with conventional post-processing methods. [5] Consequently, an alternate recipe is scrutinized to obtain an average quench field beyond 20 MV/m without reducing the high Q0 already achieved. An N-doping refinement program resulted in a N2A6 EP5 recipe, which in fact resulted into quench fields 20 MV/m. [6] As a consequence, four of the six cavities at JLab were 'reset' by removing 50 μ m from the

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Content Qo for cavities has an additional 1.4nohms residual removed for all data because of stainless steel flanged present on cavity. [2]

Cavity	Bulk chemistry	Doping round 1	Post	Reset chemistry for	Doping round 2	Post doping
ID			doping EP	baseline		EP
AES031	128µm EP	N20@26mtorrA30	$16\mu m EP$	NA	not re-doped	10µm EP
AES032	$10\mu m BCP + 123\mu m EP$	N20@26mtorrA30	$16\mu m EP$	$50\mu m EP$	N2@26mtorrA6	5μ m EP
AES033	$10\mu m BCP + 123\mu m EP$	N20@26mtorrA30	16µm EP	$50\mu m EP$	N2@26mtorrA6	5μm EP
AES034	123µm EP	N20@26mtorrA30	$16\mu m EP$	$44\mu m CBP + 50\mu m EP$	N2@26mtorrA30	$10\mu m EP$
AES035	$10\mu m BCP + 123\mu m EP$	N20@26mtorrA30	16µm EP	$45\mu m EP$	N2@26mtorrA6	5μm EP
AES036	$10\mu m BCP + 123\mu m EP$	N20@26mtorrA30	16µm EP	$50\mu m EP$	N2@26mtorrA6	5μ m EP

Table 1: Full Cavity History for Each of the 6 Nine Cells, Time Is Going from Left to Right.



Figure 2: Passband mode analysis for all quench limited tests, separated by cavity for comparison.

interior surface by EP (AES032, 33, 35 and 36), which is expected to restores the nitrogen concentration to its original level in the as-built cavity. [7] In this manner a baseline performance of the cavities can be re-establish. The baseline performance of the remaining two cavities however was omitted, i.e. one cavity received only a light EP (AES031) and another (AES034) was sent to centrifugal barrel polishing (CBP) before subsequent doping.

CAVITY RESULTS

The full cavity treatment history and 2.0 K RF performance results for all six cavities are summarized in Table 1 and Figure 1, respectively. One can see that after the reset treatment, the baseline performance for cavities AES032,033,035,036 was merely Q-slope limited without quench.² This result implies the important fact that the quench field experienced initially were due to N-doping and not cavity manufacturing. After applying the N2A6_EP5 recipe the quench fields on all the baseline cavities went up. The cavity AES031 only had marginal improvements to its π -mode quench field from its additional EP, and AES034

gradient almost doubled, but at a lower field than was expected from its lighter doping. Single cell results suggest quench field from N2A30_EP10 recipe should produce quench fields in the mid 20MV/m's [8].

In addition to finding the quench field in accelerating π -mode, RF tests were carried out by powering all other eight fundamental passband modes to investigate the quench field limits. These passband mode measurements help to determine whether an individual cell is responsible for quenching the cavity as has been the case for some early nine-cell cavities processed with un-doped ILC-style early nine-cell cavities processed with un-doped ILC-style recipes, or from multiple cell all close to the same fields. From the raw data, we then determined the averaged quench fields in all passband modes as plotted in Figure 2. A summary of all tests is listed in Table2. When the π -mode quench field is close to the average quench field and the standard deviation of the quench is relatively small, we assume that all quenches experienced in a cavity are created in a similar same way, i.e. due to the nitrogen doping. At this time the passband measurement data are not sufficient to provide a clear explanation of the quench fields experienced. As a side note, except for AES034 (see section quench localization) no cavities showed any sign of quench location from a pit-like defect verified by using JLab's high resolution long range microscope inspection system. For the given defect size in AES034 (300 nm), previous experience from ILC cavities implies the quench field at 11.2MV/m is lower than expected from its size and location. [5,9]

In order to better understand the quench differences between the two doping round, as we can't explain variation from the mode analysis alone, we attempt a simple statistical analysis treating each mode for each cavity as individual cavities. To do this we took the average of the mode averages in Table 2 for each doping and compared these averages to their standard deviations. From this very simple model it appears that changing the doping from a heavier N20A30_EP16 to a light N2A6_EP5 does not change the distribution in the cavities on average, but increases the quench fields (standard deviation percentage in yellow).

QUENCH LOCALIZATION

The two outlier cavities AES031 and AES034 were treated differently than the other cavities. For these two the

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² no 120C bake on any cavity at any time

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Table 2: π -mode and	Average Passbane	d Quench Field f	or Each Cavity Test.
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t, publisher,	Cavity ID	Doping round 1 quench field	Doping round 1 average passband quench field	Doping round 1 standard deviation from passbands	Rest quench field	Doping round 2 quench field	Doping round 2 average passband quench field	Doping round 2 standard deviation from passbands
ork	AES031	17.4MV/m	19.7MV/m	1.5MV/m	NA	19.4MV/m	27.8MV/m	5.2MV/m
e W	AES032	18.4MV/m	22.6MV/m	4.1MV/m	Q-slope	29MV/m	31MV/m	2.8MV/m
the	AES033	16.4MV/m	20.0MV/m	1.8MV/m	Q-slope	21.6MV/m	23.5MV/m	2.6MV/m
ot	AES034	11.2MV/m	17.4MV/m	3.6MV/m	NA	19.6MV/m	25.2MV/m	6.3MV/m
tle	AES035	15.3MV/m	17.0MV/m	2.6MV/m	Q-slope	23.4MV/m	24.8MV/m	2.0MV/m
, ti	AES036	17.2MV/m	21MV/m	4.0MV/m	Q-slope	24.5MV/m	28.3MV/m	1.3MV/m

e author(s Table 3: Comparison between the Average π -mode Quench Field and Average Quench Field for All Passband Modes between the Two Doping Rounds; as well a comparison between the N20A30_EP16 and N2A6_EP5 dopings.

Tests	Average π -Mode Quench Field	Standard deviation π -Mode	% Standard deviation π -Mode	Average quench field pass-bands	Standard deviation pass-bands	% Standard deviation pass-bands
Doping round 1	15.9MV/m	2.4MV/m	14.9%	19.6MV/m	2.1MV/m	10.6%
Doping round 1 without AES034	16.8MV/m	1.0MV/m	6%	20.0MV/m	2.0MV/m	10.1%
Doping round 2	23.2MV/m	3.8MV/m	16.2%	26.8MV/m	2.8MV/m	10%
N2A6 + EP5 only	25.0MV/m	1.6MV/m	6.5%	27MV/m	3.3MV/m	12%

Quenching	AES031	$\frac{16}{16}$	AES031	AES034 N2A30 F10
Cell 1	$7\pi/9.6\pi/0$)	$7\pi/9.6\pi/9$	<u>8π/97π/95π</u>
Cell 2	77, 9,07, 9	,	11, 9, 01, 9	$3\pi/9$
Cell 3				$2\pi/9$
Cell 4				
Cell 5				
Cell 6			$1\pi/9$	$\pi, 6\pi/9, 4\pi/9, 1\pi/9$
Cell 7	$5\pi/9, 2\pi/9$)	$5\pi/9, 2\pi/9$	
Cell 8	$\pi, 8\pi/9, 4\pi$ $3\pi/9$	/9,	$\pi, 8\pi/9 \ 4\pi/9 \ 3\pi/9$),
Cell 9				

AES034 quench defect in Cell 3 for doping round 1



in cell 3 of AES034 @ angle 0 right off the equator (left) and correlated temperature map (bottem) taken during RF measurements @ 2K confirming this is the quench location of the cavity.



Figure 3: Quenching defect from AES034 doping round 1.

COMMENTS

- N2A6_EP5 doping clearly produced an higher average quench field than N20A30_EP16.
- Using a very simple theoretical model, the percent gradient spread between N2A6_EP5 and N20A30 EP16 is statistically the same.
- An addition light doping of AES031 did not increase the quench field dramatically nor change the quench location, but did increase the spread, suggesting AES031 quench might be defect driven.
- Nitrogen doping recipes used so far yield lower quench fields than achieved in baseline tests (no N-doping) of a given cavity.
- There is still a lack of understanding why a given cavity quenches at a given location after N-doping, except for the special case of AES034(with identified defect site).

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the additional light EP, would the quench location change or be randomized. In this case both tests of AES031 were carried out with OST sensors to track the exact quench carried out with OST sensors to track the exact quench ised in all modes, and for the second test of AES034 OST $\frac{1}{2}$ were used to track the quenching defect in Cell 3 found by ⇒temperature mapping(see Figure 3). The exact quenching Ξ cell for the three test are shown in Table 4. For AES031, work three of the four quenching cell did not change (exact location confirmed but picture not shown), this includes the this ' limiting π mode cell 8. As for AES034 the quench in cell rom 3 in π -mode clearly changed after CBP and re-doping, and the quench in cell 3 also changed location (exact locations Content confirmed but picture not shown).

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REFERENCES

- [1] A Grassellino, A Romanenko, D Sergatskov, O Melnychuk, Y Trenikhina, A Crawford, A Rowe, M Wong, T Khabiboulline, and F Barkov. Nitrogen and argon doping of niobium for superconducting radio frequency cavities: a pathway to highly efficient accelerating structures. *Superconductor Science and Technology*, 26(10):102001, 2013.
- [2] B.P. Xiao C.E. Reece, A.D. Palczewski. An analysis of the temperature and field dependence rf surface resistance of nitrogen-doped niobium srf cavities with respect to existing theoretical models. In *IPAC2015, these proceedings*, page WEPWI021, 2015.
- [3] A. Romanenko. Breakthrough technology for very high quality factors in scrf cavities. In *LINAC14*, page Geneva. TUIOC02, 2014.
- [4] A.D. Palczewski, R.-L. Geng, and C.E. Reece. Analysis of new high-q0 srf cavity tests by nitrogen gas doping at jefferson lab. In *LINAC14 TUPP138*, page 736, 2014.

- [5] R.L. Geng et al. Gradient limiting defects in 9-cell cavities ep processed and rf tested at jefferson lab. In *Proceeding of SRF2009*, page 374, 2009.
- [6] A. Grassellino. The high q0 revolutions. In *IPAC2015, these proceedings invited Talk.*
- [7] H. Tian, A.D. Palczewski, C.E. Reece, and C. Zhou. Detailed depth profiling and surface analysis of n-doped nb for high-q0 srf cavities. In *IPAC2015, these proceedings*, page WEPWI026, 2015.
- [8] C.E. Reece and A.D. Palczewski. Report for jlab high q0 r and d for lcls-ii - fy2014. 2015.
- [9] R.L. Geng et al. Qualification of the second batch production 9-cell cavities manufactured by aes and validation of the first us industrial cavity vendor for ilc. In *Proceeding of SRF2011*, page 433, 2011.